

US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEAPPLICANT: MARTIN RICHARDSON
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA
PRODUCED FROM LIQUID METAL SOLUTIONSJc978 U.S. PTO
09/081620
06/14/01LIST OF ART CITED BY APPLICANTU.S. PATENT DOCUMENTS

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